

CLAIMS

This listing of claims replaces all prior versions, and listings, of claims in the application:

1. (previously presented): A scanning projection aligner for projecting a mask pattern for fabrication of a semiconductor device onto a substrate, said scanning projection aligner comprising:

- a reflectance measuring mechanism for irradiating an exposure adjacent area which is adjacent an exposure area of a substrate with exposure light and for measuring a reflectance of said exposure light from said exposure adjacent area when said mask pattern is projected onto said exposure area; and
- a control mechanism for adjusting an intensity of said exposure light which is irradiated onto said exposure adjacent area thereby projecting the mask pattern onto said exposure area at a predetermined intensity by referring to said measured reflectance.

2. (previously presented): The scanning projection aligner according to claim 1, wherein said reflectance measuring mechanism includes:

- an adjuster capable of adjusting an intensity of exposure light used for measurement of a reflectance; and
- a reflectance detector for measuring a reflectance of said exposure light from said substrate.

3. (previously presented): The scanning projection aligner according to claim 1, wherein said reflectance measuring mechanism includes:

- an adjuster capable of adjusting an intensity of exposure light used for measurement of a reflectance; and
- a beam splitter for branching said exposure light used for measurement of a reflectance, into two light beams; and
- two reflectance detectors each corresponding to a respective one of said two light beams.

4. (previously presented): The scanning projection aligner according to claim 1, wherein said reflectance measuring mechanism includes a branching system for branching a portion of exposure light emitted from an exposure light source.

5. (currently amended): ~~A~~The scanning projection aligner according to claim 1, for projecting a mask pattern for fabrication of a semiconductor device onto a substrate, said projection aligner comprising:

~~a reflectance measuring mechanism for irradiating a substrate with exposure light and measuring a reflectance of said exposure light from said substrate; and~~

~~a control mechanism for adjusting an intensity of said exposure light to a predetermined intensity by referring to said measured reflectance,~~
wherein said reflectance measuring mechanism includes an optical system for forming exposure light used for measurement of a reflectance, into a beam of a predetermined shape.

6. (previously presented): The scanning projection aligner according to claim 1, wherein said control mechanism includes a determining system for determining an intensity of appropriate exposure light from said measured reflectance based on data indicating relationships between reflectances and intensities of appropriate exposure light.

7. (previously presented): The scanning projection aligner according to claim 1, wherein said control mechanism includes a changing system for changing illumination of an illumination system which provides exposure light.

8. (previously presented): The scanning projection aligner according to claim 1, further comprising:

a pulse light source as an exposure light source;
wherein said control mechanism includes a changing system for changing an interval between pulse light emissions.

9. (previously presented): The scanning projection aligner according to claim 1, wherein said control mechanism includes a changing system for changing a scan speed of a stage for moving a substrate against exposure light.

10. (Withdrawn): A projection exposure method comprising:

- a first step of, from an exposure light source, irradiating a substrate with exposure light, and measuring a reflectance of said exposure light from said substrate; and
- a second step of determining an appropriate intensity of exposure light for said substrate based on said reflectance, and then projecting a mask pattern onto said substrate by irradiating with exposure light of said determined intensity.

11. (Withdrawn): The projection exposure method according to claim 10, wherein said first step irradiates an exposure area of a substrate with exposure light beforehand and measures a reflectance of said exposure light from said substrate, said exposure light having energy lower than that of exposure light at a time of a projection exposure.

12. (Withdrawn): The projection exposure method according to claim 10, wherein said first step includes steps of:

- branching a portion of exposure light from an exposure light source at a time of projecting a mask pattern onto an exposure area;
- irradiating an area adjacent to said exposure area of said substrate with said branched light; and
- measuring a reflectance of said branched light from said substrate.

13. (Withdrawn): The projection exposure method according to claim 10, wherein said first step includes steps of:

- branching a portion of exposure light from an exposure light source at a time of projecting a mask pattern onto an exposure area;
- irradiating an area immediately before said exposure area of said substrate with said branched light; and

measuring a reflectance of said branched light from said substrate.

14. (Withdrawn): The projection exposure method according to claim 10, wherein said first step includes steps of:

forming a portion of exposure light from an exposure light source into a beam of a predetermined shape by use of an optical system;
irradiating a substrate with said beam; and
measuring a reflectance of said beam from said substrate.

15. (Withdrawn): The projection exposure method according to claim 10, wherein said first step includes steps of:

branching a portion of exposure light from an exposure light source;
branching said branched light into two light beams; and
measuring a reflectance of a branched light beam selected from said two branched light beams, said selected branched light beam illuminating an area which is immediately before an exposure area and is determined based on a moving direction of a substrate.

16. (Withdrawn): The projection exposure method according to claim 10, wherein said second step includes steps of:

preparing data indicating relationships between reflectances of a substrate and appropriate intensities of exposure light; and
determining an appropriate intensity of exposure light at a time of an exposure by referring to said data based on reflectance measuring results.

17. (Withdrawn): The projection exposure method according to claim 10, wherein, in said second step, said substrate is irradiated with exposure light of said appropriate intensity by changing illumination of said exposure light.

18. (Withdrawn): The projection exposure method according to claim 10, wherein, in said second step, said substrate is irradiated with exposure light of said appropriate intensity by changing an interval between pulse light emissions of said exposure light.

19. (Withdrawn): The projection exposure method according to claim 10, wherein, in said second step, said substrate is irradiated with exposure light of said appropriate intensity by adjusting a scan speed of a wafer stage on which said substrate is mounted.

20. (Withdrawn): A semiconductor device fabricated by use of the projection exposure method according to claim 10.